

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
1	BRS	L1	40	spiegelman-j\$.in.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:13	
2	BRS	L2	119	alvarez-d\$.in.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:13	
3	BRS	L3	0	tram-a\$.in.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:13	
4	BRS	L4	143	11 or 12	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:13	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
5	BRS	L5	0	(ultra adj clean adj dry adj air) with (contaminant or impurity or contamination or AMC)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBMTDB; USOCR	2004/07/13 09:14	
6	BRS	L6	0	(ultra adj clean adj dry adj air or "XCDA") with (contaminant or impurity or contamination or AMC)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBMTDB; USOCR	2004/07/13 09:15	
7	BRS	L7	2	(ultra adj clean adj dry adj air or "XCDA")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBMTDB; USOCR	2004/07/13 09:18	
8	BRS	L9	7	18 and (purif\$3 adj3 gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBMTDB; USOCR	2004/07/13 09:23	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
9	BRS	L10	10	l4 and (purif\$3 adj gas)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 09:26	
10	BRS	L11	45	(remove or removing or removed or removal) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) adj10 (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 09:42	
11	BRS	L12	24	(eliminate or eliminated or elimination or eliminating or treat or treating or treated or treatment) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) adj10 (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 09:42	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
12	BRS	L13	49	(clean or cleaning or cleaned or cleanse or cleansing or cleansed or flush or flushing or flushed or purge or purged or purging or dislodge or dislodging or dislodged or loosen or loosening or loosened) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) adj10 (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM-TDB; USOCR	2004/07/13 09:43	
13	BRS	L14	2	(strip or stripping or stripped or stripper) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) adj10 (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM-TDB; USOCR	2004/07/13 09:43	
14	BRS	L15	121	110 or 111 or 112 or 113	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM-TDB; USOCR	2004/07/13 09:32	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
15	BRS	L16	10	l15 and(purif\$3 adj3 gas)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:32	
16	BRS	L17	113	l14 or l11 or l12 or l13	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:32	
17	BRS	L18	0	l17 and(purif\$3 adj3 gas)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:32	
18	BRS	L19	49356	(134/\$).ccls.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:32	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
19	BRS	L20	9	117 and 119	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 09:32	
20	BRS	L21	363	(remove or removing or removed or removal) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) same (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 09:57	
21	BRS	L22	105	(eliminate or eliminated or elimination or eliminating or treat or treating or treated or treatment) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) same (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 09:59	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
22	BRS	L23	216	(clean or cleaning or cleaned or cleanse or cleansing or cleansed or flush or flushing or flushed or purge or purged or purging or dislodge or dislodging or dislodged or loosen or loosening or loosened) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) same (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 10:35	
23	BRS	L24	9	(strip or stripping or stripped or stripper) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) same (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 10:00	
24	BRS	L25	647	121 or 122 or 123 or 124	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:46	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
25	BRS	L26	15	125 and ((pure or purif\$) adj3 (gas or nitrogen or oxygen or "N2" or "N.sub.2" or "O.sub.2" or "O2"))	USPAT; US-PGPUB; ; EPO; JPO; DERWENT; IBM_TDB; USOCR	2004/07/13 10:03	
26	BRS	L27	503	(remove or removing or removed or removal or condition or conditioning or conditioned or sterilize or sterilizing or sterilized or sterilization or sanitize or sanitizing or sanitized) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) same (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor or container or clean-room\$ or clean adj room\$ or enclosure)	USPAT; US-PGPUB; ; EPO; JPO; DERWENT; IBM_TDB; USOCR	2004/07/13 09:59	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
27	BRS	L28	122	(eliminate or eliminated or elimination or eliminating or treat or treating or treated or treatment) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) same (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor or container or clean-room\$ or clean adj room\$ or enclosure)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 09:59	
28	BRS	L29	278	(clean or cleaning or cleaned or cleanse or cleansing or cleansed or flush or flushing or flushed or purge or purged or purging or dislodge or dislodging or dislodged or loosen or loosening or loosened) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) same (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor or container or clean-room\$ or clean adj room\$ or enclosure)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 10:00	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
29	BRS	L30	9	(strip or stripping or stripped or stripper) adj10 (airborne) adj3 (contamination or contaminant or particle or particulate or impurity) same (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor or container or clean-room\$ or clean adj room\$ or enclosure)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 10:03	
30	BRS	L31	839	127 or 128 or 129 or 130	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 10:03	
31	BRS	L32	88	131 and ((pure or purif\$) adj3 (air or gas or nitrogen or oxygen or "N2" or "N.sub.2" or "O.sub.2" or "O2"))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 10:38	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
32	BRS	L33	1240110	(clean or cleaning or cleaned or cleanse or cleansing or cleansed or flush or flushing or flushed or purge or purged or purging or condition or conditioning or conditioned or treat or treating or treated or treatment or strip or stripping or stripped or sterilize or sterilizing or sterilized or sanitize or sanitized or sanitizing) adj10 (surface or object or semiconductor or wafer or substrate or chamber or vessel or reactor or container or pod or fab or enclosure)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:50	
33	BRS	L34	1540	133 with((pure or purif\$) adj3 (air or gas or nitrogen or oxygen or "N2" or "N.sub.2" or "O.sub.2" or "O2"))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 10:40	
34	BRS	L35	3849	((pure or purif\$) adj3 (air or gas or nitrogen or oxygen or "N2" or "N.sub.2" or "O.sub.2" or "O2")) adj10 (water or "H2O" or "H.sub.2O")	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 10:40	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
35	BRS	L36	4276	((pure or purif\$) adj3 (air or gas or nitrogen or oxygen or "N2" or "N.sub.2" or "O.sub.2" or "O2")) adj10 (water or "H2O" or "H.sub.2O" or water adj vapor or moisture)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 11:12	
36	BRS	L38	2	119 and 137	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 10:40	
37	BRS	L37	69	133 with 136	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 11:00	
38	BRS	L39	23878	((pure or purif\$) adj3 (air or gas or nitrogen or oxygen or "N2" or "N.sub.2" or "O.sub.2" or "O2")) same (water or "H2O" or "H.sub.2O" or water adj vapor or moisture)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 10:44	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
39	BRS	L40	1669	133 same 139	USPAT; US-PGPUB; ; EPO; JPO; DERWENT; IBM_TDB; USOCR	2004/07/13 11:00	
40	BRS	L41	102	140 and 119	USPAT; US-PGPUB; ; EPO; JPO; DERWENT; IBM_TDB; USOCR	2004/07/13 11:00	
41	BRS	L42	5048	((pure or purif\$) adj3 (air or gas or nitrogen or oxygen or "N2" or "N.sub.2" or "O.sub.2" or "O2")) adj10 (water or "H2O" or "H.sub.2O" or water adj vapor or moisture or steam)	USPAT; US-PGPUB; ; EPO; JPO; DERWENT; IBM_TDB; USOCR	2004/07/13 12:59	
42	BRS	L43	2	5846338.pn.	USPAT; US-PGPUB; ; EPO; JPO; DERWENT; IBM_TDB; USOCR	2004/07/13 11:40	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
43	BRS	L44	1467	((control\$3) adj10 (vent\$3)).ti.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 11:43	
44	BRS	L45	2	119 and 144	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 11:41	
45	BRS	L46	160	144 and ((chamber or reactor or container) same (flow\$3))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 11:43	
46	BRS	L47	18693	((chamber or reactor or container) same (flow\$3)) same ("venting")	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/1 3 11:44	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
47	BRS	L48	118	((chamber or reactor or container) same (flow\$3)) same ("controlled venting")	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:46	
48	BRS	L49	52	("controlled venting").ti.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:45	
49	BRS	L50	49	149 not ("air bag")	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:46	
50	BRS	L51	5	((chamber or reactor or container) same (flow\$3)) and 149	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:47	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
51	BRS	L52	210	venting same (load adj lock or loadlock or load-lock)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:48	
52	BRS	L53	4	venting.ti. same (load adj lock or loadlock or load-lock)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:48	
53	BRS	L54	32877 7	(clean or cleaning or cleaned or cleanse or cleansing or cleansed or flush or flushing or flushed or purge or purged or purging or condition or conditioning or conditioned or treat or treating or treated or treatment or strip or stripping or stripped or sterilize or sterilizing or sterilized or sanitize or sanitized or sanitizing or vent or venting or vented) adj10 (chamber or clean-room adj container or cleanroom adj container or load-lock or loadlock or reactor or vessel)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:52	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
54	BRS	L55	128	154 same 142	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:55	
55	BRS	L56	34	154 with 142	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:53	
56	BRS	L57	4	154 adj10 142	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:55	
57	BRS	L8	14	aeronex-\$.asn.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:56	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
58	BRS	L58	2	14 and 142	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:58	
59	BRS	L59	2	18 and 142	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 11:58	
60	BRS	L60	6	markoff and 134/\$.ccls. and wafer and steam	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 13:02	
61	BRS	L61	22839	steam and (water adj (content or concentration))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB; USOC R	2004/07/13 13:03	